

23rd International Microprocesses and Nanotechnology Conference MNC 2010

Veranstaltung - 23rd International Microprocesses and Nanotechnology Conference MNC 2010 ♪

Titel	23rd International Microprocesses and Nanotechnology Conference MNC 2010
Wann	Di, 9. November 2010 - Fr, 12. November 2010

Beschreibung

23rd International Microprocesses and Nanotechnology Conference MNC 2010

You are encouraged to submit a paper of your recent research.

Conference Name:

[23rd International Microprocesses and Nanotechnology Conference \(MNC 2010\)](#)

DATE: November 9-12, 2010

PLACE: Rihga Royal Hotel Kokura, Japan

Sponsored by The Japan Society of Applied Physics

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Prospective authors are requested to submit following materials through [MNC 2010 web site](#).

- Two-Page abstract in PDF together with Copyright Transfer Form. The paper submission system will be operated from June 5, 2010.

+++++ CONFERENCE SCOPE ++++++

1. Lithography and Related Technologies
 - 1-1. DUV, EUV Lithography and Metrology
 - 1-2. Electron- and Ion-Beam Lithography
 - 1-3. Resist Materials and Processing
2. Nanotechnology
 - 2-0. Nanocarbon
 - 2-1. Nanodevices
 - 2-2. Nanofabrication
 - 2-3. Nanomaterials
 - 2-4. Nanotool
3. Nanoimprint, Nanoprint and Rising Lithography
4. BioMEMS, Lab. on a Chip
5. Microsystem Technology and MEMS

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